Y-junction power splitter enhanced through subwavelength metamaterials

Raquel Fernández de Cabo Instituto de Óptica Consejo Superior de Investigaciones Científicas Madrid, Spain r.fernandez@csic.es David González-Andrade Instituto de Óptica Consejo Superior de Investigaciones Científicas Madrid, Spain david.gonzalez@csic.es

Abstract— We present a Y-junction beam splitter based on subwavelength metamaterials that circumvents losses associated to the fabrication limitations in the tip size of traditional Y-junctions. Simulations show excess losses under 0.5 dB for TE_0 and TE_1 in a 300 nm range (1300 - 1600 nm).

Keywords—Photonic integrated circuits, Silicon photonics, Power division, Y-junction, Subwavelength, Minimum feature size.

I. INTRODUCTION

Efficient power splitting is a fundamental need in siliconbased photonic integrated circuits (PICs) [1], with applications in mode-division multiplexing [2], optical phased arrays [3], or microspectrometers [4], to name a few. Y-junctions, consisting of a stem waveguide which branches into two diverging arms, are one of the most widespread beam splitters [5]. In symmetrical configurations, Y-junction theoretically work as a perfect power divider for both the fundamental mode and the first-order mode. However, the finite resolution of current micro fabrication methods results in a limited minimum feature size (MFS) of the junction tip between the splitter arms [5]. This deviation from the nominal design particularly penalizes fundamental mode losses, as their energy peak is located in the central region.

In order to reduce losses and improve bandwidth of PIC components, subwavelength gratings (SWG) were proposed [6]. SWG are segmented waveguides with a grating period (Λ) significantly smaller than the wavelength (λ) of propagating light. Under this condition, the medium behaves as a homogeneous metamaterial [7], whose optical properties (e.g. effective index, dispersion, anisotropy) can be tailored through geometric design. This approach has been successfully applied to mode-division multiplexing and microspectrometers [2, 4], among many others.

In this work, we propose the application of SWG technology to Y-junctions, effectively reducing mode confinement around the junction tip and hence circumventing minimum feature size penalization on the fundamental mode. Our device exhibits simulated excess losses (EL) as low as 0.5 dB for the fundamental transverse electric mode (TE₀) and the first-order transverse electric mode (TE₁) in a 300 nm bandwidth (1300 -1600 nm). Pavel Cheben Institute for Microstructural Sciences National Research Council Canada Ottawa, Canada Pavel.Cheben@nrc-cnrc.gc.ca Aitor V. Velalsco Instituto de Óptica Consejo Superior de Investigaciones Científicas Madrid, Spain a.villafranca@csic.es

II. DEVICE OPERATION

In order to compare our solution to a traditional approach, we consider as a reference a non-periodic Y-junction, whose scheme is shown in Fig. 1(a). This device comprises a multimode input stem of width W_0 and length L_s , and two monomode S-shaped output arms of width $W=W_0/2$, length L_B . and final separation H_a . We consider a gap between the arms at the junction tip, of width H_{off} which accounts for the MFS limitation in the fabrication process. A taper of length L_T at the input and straight section of length L_0 at the output are also included. Exciting the stem with TE₁ mode results in almost loss-free power splitting as a consequence of the zero-power profile of this mode through the center of the stem, but losses are significantly increased for TE₀ mode in the presence of the junction gap, further increasing the larger H_{off} is.

Our device incorporates SWG metamaterials to both the arms and the stem, while preserving the same arm offset, and hence the same MFS (Fig. 1(b)). Arm widths and separation are also maintained. The device starts with a strip waveguide of length L_I and width W_S that evolves into a SWG waveguide of length L_C through an adiabatic taper. This SWG region induces



Fig. 1. Schematic of the state-of-the-art non-periodic (a) and the proposed SWG Y-junction (b). Propagation of fundamental and first-order modes along the device is also shown.

This work has been funded in part by the Spanish Ministry of Science, Innovation and Universities (MICINN) under grants RTI2018-097957-B-C33 and TEC2015-71127-C2-1-R (FPI BES-2016-077798) and the Community of Madrid – FEDER funds (S2018/NMT-4326). This project has received funding from the Horizon 2020 research and innovation program under Marie Sklodowska-Curie grant No. 734331.

a lesser mode confinement in order to reduce the radiation in the junction tip for TE₀. Another advantage of SWG is the possibility to perform dispersion engineering through the modification of the pitch and the silicon segments length. Moreover, to optimize transmission in the interface between the stem and the arms, we define different duty cycles on both sides, $DC_S=a_S/\Lambda$ and $DC_A=a_A/\Lambda$, where a_S is the silicon segment length in the stem and a_A is the silicon segment length in the arms, respectively, considering a constant period.

III. DEVICE DESIGN

We optimized our device for a silicon-on-insulator platform with a waveguide core thickness of 220 nm, with upper and bottom silicon dioxide cladding. The refractive index of each material is approximately $n_{Si} \sim 3.48$ and $n_{SiO2} \sim 1.44$, for a wavelength of $\lambda \sim 1.55 \mu$ m. An arm width of W = 500 nm is selected in order to ensure the arms are monomode, while a stem width of $W_s = 1200$ nm provides an increased effective index of the stem that reduces interface reflections. An SWG pitch of $\Lambda = 220$ nm is set to avoid Bragg-reflection, while a DC_s of 50% facilitates the fabrication process. We consider a H_{off} of 100 nm for the worst-case scenario regarding manufacturing accuracy limitations, preserving this same limit as MFS for the whole design. A complete list of the others geometrical design parameters can be found in Table I.

TABLE I. PARAMETER VALUES

Design	Parameter	Symbol	Value
SWG and Non- periodic Y- junction	Arms width	W	0.5 µm
	Arms output separation	H_a	1.5 μm
	Arm length	L_B	9.8 µm
Non-periodic Y- junction	Stem guide length	L_S	13 µm
	Taper length	LT	4 µm
	Output-section length	Lo	9 µm
	Taper final width	W_T	1.1 μm
SWG Y-junction	Input strip width	W_S	1.2 μm
	Input strip length	L_I	3 µm
	Input SWG taper	Lti	10 µm
	Output SWG taper	Lto	6 µm
	Central SWG section	L_C	13 µm
	Output strip length	L_E	3 µm

IV. SIMULATION RESULTS

The device performance was simulated through 3D-FDTD simulation. In order to optimize excess losses (EL), i.e. the relation between the optical power at the output arms in relation to the power injected in the input stem, we swept DC_A while holding DC_S constant. We found minimum EL for TE₁ at DC_A = 55%, while EL for TE₀ presents a flatter response against DC_A starting around the same value. Note that this DC value imposes a separation between SWG segments in the arms of 100 nm, thus respecting MFS.

Excess loss obtained for the SWG device and for the reference non-periodic counterpart are shown in Fig. 2. Our



Fig. 2. Excess loss comparision between SWG and non-periodic Yjunction for TE_0 and TE_1 modes.

design exhibits a significant reduction in TE₀ excess losses at the nominal wavelength of 1550 nm (from 0.99 dB down to 0.12 dB). Despite a slight increase of TE₁ excess losses (from 0.07 dB up to 0.40 dB), the sum of both EL values is significantly smaller in the SWG device, which also provides a more even performance for both modes. This behavior is preserved in a very broad bandwidth, as simulations show EL under 0.5 dB for both TE₀ and TE₁ in a 300 nm bandwidth (1300 - 1600 nm).

V. CONCLUSIONS

We have proposed a high-performance power splitter based on a Y-junction enhanced through subwavelength metamaterials, which reduces fundamental mode losses caused by fabrication limitations at the junction tip. Simulations show insertion losses as low as 0.5 dB for TE₀ and TE₁ in a 300 nm bandwidth (1300 - 1600 nm). We believe that the proposed optical beam splitter will find numerous applications in diverse photonic integrated circuits, and particularly, in mode-division multiplexing applications.

REFERENCES

- L. Chrostowski, *et al.*, Silicon photonics design: from devices to systems, Cambridge University Press, 2015.
- [2] D. González-Andrade, *et al.*, "Ultra-Broadband Mode Converter and Multiplexer Based on Sub-Wavelength Structures," IEEE Photon. J., vol. 10, p. 2201010, 2018.
- [3] J. K. Doylend, *et al*, "Two-dimensional free-space beam steering with an optical phased array on silicon-on-insulator," Opt. Express, vol. 19, pp. 21595-21604, 2011.
- [4] A. Herrero-Bermello, et al., "On-chip Fourier-transform spectrometers and machine learning: a new route to smart photonic sensors," Opt. Lett., vol. 44, pp. 5840-5843, 2019.
- [5] Y. Zhang, et al., "A compact and low loss Y-junction for submicron silicon waveguide," Opt. Express, vol. 21, pp. 1310-131, 2013.
- [6] P. Cheben, et al., "Subwavelength integrated photonics," Nature, vol. 560, pp. 565–572, 2018.
- [7] P. Lalanne, *et al.*, "High-order effective-medium theory of subwavelength gratings in classical mounting: application to volume holograms," J. Opt. Soc. Am. A., vol. 15, pp.1843-1851, 1998.